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APPLICANT
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U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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et al.: ANALYSIS OF DEPOSITION RATE DISTRIBUTION IN THE PHOTO-CVD OF a-Si
BY A UNIFIED REACTOR WITH A LAMP, pp. L776-L778.

EXAMINER

George Gunderson

DATE CONSIDERED

8-93

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